

Notice of References Cited	Application/Control No. 10/605,607	Applicant(s)/Patent Under Reexamination HO ET AL.	
	Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,770,484	06-1998	Kleinhenz, Richard Leo	438/155
	B	US-2004/0147074	07-2004	Sell et al.	438/243
	C	US-6,472,702	10-2002	Shen, Wei-Lin	257/301
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	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

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	U	Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, p. 198.
	V	Wolf, Silicon Processing for the VLSI Era, 2002, Lattice Press, Vol. 4, pp. 535-36.
	W	Wolf et al., Silicon Processing for the VLSI Era, 1986, Lattice Press, Vol. 1, pp. 523-24.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.